ULTRA t Equipment Models PRD408

DESCRIPTION:

The ***highly efficient*** Model PRD408 is the ideal solution for automatic batch develop and rinse of positive resist on wafers and photomask. This ***very reliable*** and ***cost effective*** system utilizes one process tank for both develop and rinse for Rapid and Effective processing of wafers. Rapid fill and evacuation of both Developer and D.I. Water provides for precise control of cycle times. The developer is continuously filtered and automatically replenished and the temperature is accurately maintained for reliable and repeatable process.

FEATURES:

- Up to Eight (8) Inch Wafer Compatibility
- High Volume Developer Fill for Rapid Emersion of Wafers and Engineered to Minimize Foaming
- Temperature Range of 50° to 100° F with Resolution at ±0.3^o F
- Adjustable Mechanical Agitation for Uniform Developing
- Large Quick Dump Valve for Rapid Evacuation of Developer at End of Develop Cycle
- Six DI Water Spray Nozzles for Fast Effective Termination of Develop Cycle
- Rapid Fill and Dump of D.I. Water for Fast Cycle
- Spray Assembly using Reservoir Developer for Elimination of Water from Process Tank and Maintenance of Developer Normality
- Nitrogen Barrier at Reservoir for Developer Isolation
- Automatic Replenish for Maintenance of Normality
- 0.45 µm Filtration of Developer
- Programmable Microprocessor Controlled

OPTIONS:

- Dual 5 Gallon Developer Dispense Canister with Level Alert

SPECIFICATIONS:

Developer Capacity
- Reservoir: 13 Gallons
- Process Tank: 7.5 Gallons

Process Tank: 15.5" W x 10.5" D x 11" H

Baskets 8” Wafer: 9" W x 9" D

$\leq$ 6” Wafer: 13” W x 6.6” D

FACILITIES REQUIREMENTS:

Power:	Varies with System
D.I. Water:	5 GPM
Nitrogen:	50 PSI & 0.1 CFM min.
Drain:	5 GPM Intermittent
Dimensions:	39” W x 33” D x 55” H
Weight:	= 500 Pounds

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